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Locally hosted by
Shanghai Institute of
Ceramics, Chinese Academy
of Sciences (SICCAS)

General Theme

The 2nd International Symposium on Innovations in Advanced Materials for Optics & Electronics (ISIAMOE-2) will be held in Shanghai China on July 2008. The purpose of our symposium is to bring together researchers from different fields of academic and applied science in order review and update the present knowledge on the correlation between the chemical composition, the structure and the physical properties of materials of interest for optics and electronics. The first symposium successfully established at Université de La Rochelle (France) on June 14-17, 2006. The symposium working language is English, and the program includes Poster Communications, Oral presentations, Invited Contributions and keynote Lectures.

Call for Papers:

Interested authors should send abstract/abstracts to the Symposium through the [symposium entry \(to register and submit on line\)](#) before abstracts submission deadline. Please prepare the abstract according to the abstrat file format as listed in the [symposium topics](#) column. Publication of symposium proceedings is planned after the conference.

Latest News:

1. The ISIAMOE-2 abstract submission deadline has been postponed to **April 20, 2008**. Please submit your abstract in time.

Download:

1. The Third Announcement and Call for Papers ([English](#), [Chinese](#))
 2. [Abstract Sample](#).
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Important Dates:

| | |
|----------------|--|
| Oct. 20, 2007 | Start to submit your paper abstract |
| Apr. 20, 2008 | Abstract submission deadline |
| May. 6, 2008 | Abstract acceptance notification |
| Jun. 20, 2008 | Deadline for paying discount registration fees |
| July 6-9, 2008 | Attending the symposium |

Registration fee :

For authors from outside mainland of China, the registration fee is US\$400 per person. If the registration fee is paid before June 20, 2008, a discount fee of only US\$350 is needed. The registration fee for student is US\$250. Further details of the registration fees and benefits will be provided later in our entry system after you register and log in to submit an abstract.

Organisers:



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